

3 wherein said well region includes a first well portion
4 and a second well portion,

5 wherein said first mask pattern data includes fourth
6 mask pattern data and fifth mask pattern data,

E1
7 wherein said fourth mask pattern data is for
8 determining a figure pattern for forming the first well
9 portion, and

10 wherein said fifth mask pattern data is for
11 determining a figure pattern for forming the second well
12 portion.

Please add the following claims:

E2
1 60. (New) A design data recording medium according
2 to claim 37, wherein said second mask pattern includes a
3 figure pattern for forming said first line pair and said
4 second line pair in parallel.

1 61. (New) A design data recording medium according
2 to claim 38, wherein descriptions for the first logic gate
3 and the second logic gate have description of said first
4 line pair and said second line pair in common.
